

ABSTRACT

There is provided a secondary reactive termination circuit connected between the output of the RF power generator and the input of the plasma chamber to allow the

5 tight regulation or limiting of the voltage and current components of the secondary frequencies within the process plasma. The secondary reactive circuit controls the impedance of the match network designed primarily to operate at the fundamental frequency of the RF power generator as seen by secondary frequencies in the system. A variable capacitor gives the operator the advantage of being able to tightly regulate

10 the voltage, current, and power within a process at discrete frequencies without concern for impedance variability induced by other components in the system.

15